Photosensitive Materials with Zirconia Nanotechnology

*Hiroki Chisaka¹, Kouichi Misumi¹, Dai Shiota¹, Katsumi Ohmori¹, Lei Zheng², Robert J. Wiacek², Z. Serpil Gonen Williams² (1. Tokyo Ohka Kogyo Co., Ltd. (Japan), 2. Pixelligent Technologies LLC (United States of America))

Keywords: High reflective index (HRI), Zirconia (ZrO₂), Flexible, Photo-patternenable, Inkjet

The combination of ZrO₂ nanocrystals and photosensitive technologies led to new photosensitive materials and inks with high refractive index and inkjet properties superior to conventional materials. Moreover, high resolution and high transparency was achieved even with thick films. This material is useful for next generation applications such as flexible displays.